

LIGHT COUPLING MECHANISMS IN QUANTUM WELL INFRARED PHOTODETECTOR FOCAL PLANE ARRAYS

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Quantum Well Infrared Photodetectors (QWIPs) do not absorb radiation incident normal to the surface since the light **polarization** must have an electric field component normal to the **superlattice** (growth direction) to be absorbed by the confined carriers [1]. When the incoming light contains no polarization component along the growth **direction**, the matrix element of the interaction vanishes (i.e., $\vec{\epsilon} \cdot \vec{p}_z = 0$ where $\vec{\epsilon}$ is the polarization and \vec{p}_z is the momentum along z direction). As a consequence, these detectors have to be **illuminated** through a 45° polished **facet** [1]. Clearly, this illumination scheme limits the **configuration** of detectors to linear arrays and single elements. For imaging, it is necessary to be able to couple light **uniformly** to two dimensional arrays of these detectors. Several different monolithic grating structures [1], such as linear gratings, two-dimensional (2-D) periodic **gratings**, and random-reflectors have been demonstrated for efficient light coupling to QWIPs, and has made two dimensional QWIP imaging arrays [2] feasible. These gratings deflect the incoming light away from the direction normal to the **surface**, enabling **intersubband** absorption. All these gratings were **fabricated** on the detectors by using standard photolithography and selective dry etching. The advantage of **the photolithographic** process is its ability to accurately control the **feature** size and to preserve the pixel-to-pixel **uniformity**, which is a prerequisite for high-sensitivity imaging focal plane array (**FPA**). However the resolution of the photolithography and the accuracy of etching processes become key issues in producing **smaller** grating feature **sizes**. These feature sizes are proportionally scaled with the peak response wavelength of the **QWIP**. It is important to note that for any given wavelength the random **grating** requires much **smaller** feature sizes than two dimensional periodic gratings. Thus the random reflectors of the 9 μm cutoff FPA were less sharp and had fewer scattering centers compared to 15 μm cutoff FPA and this is due to the difficulties associated with sub-micron photolithography. These **less** sharp features in random gratings lowered the light coupling efficiency than expected. Thus, it could be advantageous to utilize a 2-D periodic grating for light coupling in shorter wavelength **QWIPs**.

Six **different** 2-D grating periods were fabricated on a standard QWIP structure designed to **perform** at peak wavelength, λ_p - 8.5 μm . In order to **fabricate** three QWIP samples with three different grating groove depths for each grating period, the top cap layer of each sample was thinned down to a different thickness by chemical etching. As a control sample, a standard 45° edge polished facet sample was also fabricated from the original **QWIP** wafer. We have observed an enhancement **factor** of three due to 2D periodic grating **fabricated** on **QWIP** structure. Variation of the enhancement factor with groove depth and feature size of the grating can be theoretically explained. However the resolution of the photolithography and accuracy of the etching become key issues **in**

producing smaller grating feature sizes especially in shorter wavelengths. Unlike random **reflectors** the tight coupling efficiency of two dimensional (2-D) gratings strongly depends on the wavelength and thus exhibits narrow band width spectral responses. Therefore, 2-D gratings can **be** utilized to select narrow spectral bands in multi color QWIP cameras.

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